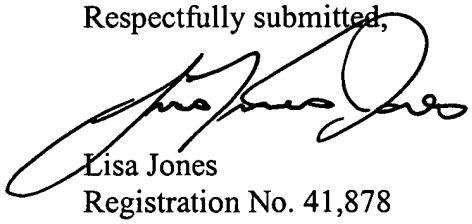
$(C_3R_3)_mMX_n$

wherein $(C_3R_3)$is a cyclopropenyl ring and each R is a monodentate or a bidentate radical and is independently hydrogen, hydrocarbyl, substituted-hydrocarbyl, halocarbyl, substituted-halocarbyl, hydrocarbyl-substituted organometalloid, halocarbyl-substituted organometalloid, disubstituted boron, disubstituted pnictogen, substituted chalcogen or halogen, and when R is a bidentate radical it may form a C_4 to C_{20} ring system to give a saturated or unsaturated polycyclic cyclopropenyl ligand or it may form a bridge between one (C_3R_3) and another (C_3R_3) or an X radical; each X radical is independently a halide, hydride , hydrocarbyl, substituted hydrocarbyl, halocarbyl, substituted halocarbyl, and hydrocarbyl- and halocarbyl-substituted organometalloid, substituted pnictogen, or substituted chalcogen and one X may be a pi-bonded cyclopentadienyl or a cyclopentadienyl-derived ligand and one X may be an amido or an imido radical; M is a Group 3, 4, 5, 6, 8, 9 or 10 transition metal, and m and n are integers of 1 or greater and m+n satisfies the valence of M.

If it would be of assistance to resolve any outstanding issues in the present application, the Examiner is invited to contact the undersigned.

Respectfully submitted,



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